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1725

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. Of: TANABE et al.

Serial No.: 09/612,551

Filed: July 7, 2000

For: SEMICONDUCTOR THIN FILM FORMING SYSTEM

Group: 1725

Examiner: GEOFFREY S. EVANS

DOCKET: NEC WNZ-2212

Assistant Commissioner of Patents and Trademarks  
Washington, D.C. 20231

**AMENDMENT D**

Dear Sir:

The following Amendment is being filed in response to the Official Action mailed December 5, 2002.

Please amend the Application as follows:

**IN THE TITLE:**

Please amend the title to read as follows:

--A SYSTEM FOR THE FORMATION OF A SILICON THIN FILM AND A  
SEMICONDUCTOR-INSULATING FILM INTERFACE--

**IN THE CLAIMS:**

Please amend claims 1 and 17-22 to read as follows:

1. (Twice Amended) A semiconductor thin film forming method comprising:

modifying a predetermined region of a semiconductor thin film by exposing the semiconductor thin film to a projected light patterned through plural patterns formed on a photo mask; and

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